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DATE:

October 4, 2004

FILE NO:

AMAT/3032.C7/DSM/LOW K/JW

TO:

Examiner: Thao P. Le

FAX NO:

703-872-9306

COMPANY:

USPTO

FROM:

Keith M. Tackett

PAGE(S) with cover:

8

ORIGINAL TO

FOLLOW?

☐ YES ☒ NO

RESPONSE TO FINAL OFFICE ACTION DATED AUGUST 6, 2004

TITLE:

Plasma Processes for Depositing Low Dielectric Constant

Films

U.S. SERIAL NO .:

10/647,959

FILING DATE:

August 26, 2003

INVENTOR:

Cheung, et al.

EXAMINER:

Thao P. Le

GROUP ART UNIT:

2818

CONFIRMATION NO.:

5142

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